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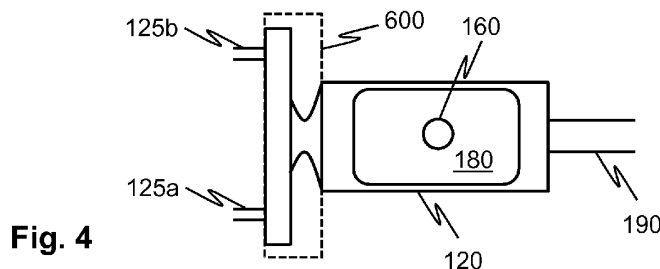
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(54) **Title:** A THIN-FILM DEPOSITION APPARATUS FOR BATCH PROCESSING



(57) **Abstract:** A substrate processing apparatus (100), comprising a reaction chamber (120) configured to accommodate a batch of substrates (130) arranged with their surfaces facing each other thus forming a substrate stack, and a fluid distributor (600) for establishing a fluid flow to the reaction chamber (120), wherein the fluid distributor (600) is configured to spread the fluid flow in a height direction of the substrate stack so as to enable a laminar flow to be developed within the reaction chamber to propagate through the length of said reaction chamber and the substrate stack

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